

# DLTS measurements of Epitaxial and MCZ silicon detectors after 26 MeV proton irradiation

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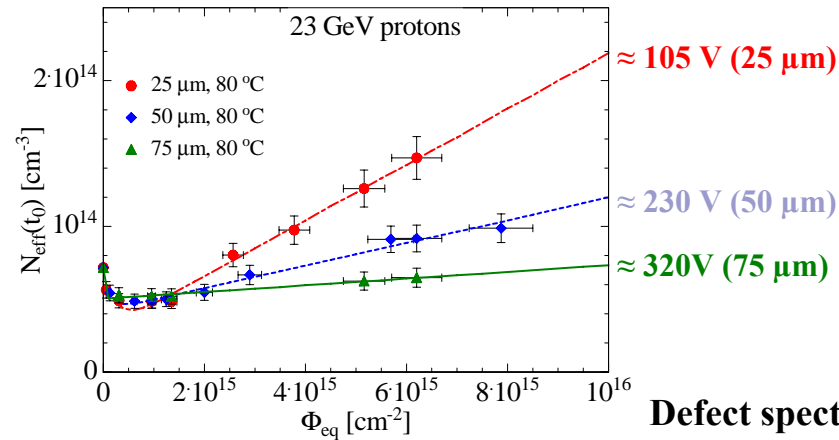
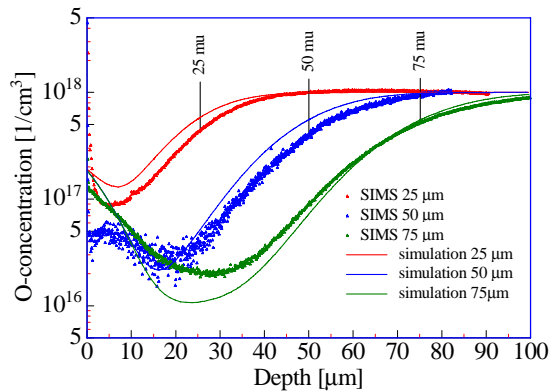
# Outline

- **Motivation**
- **Material properties**
- **Experimental methods**
- **Measurements and results**
- **Conclusions**



# Shallow Donors, the real issue for EPI

## -Comparison of 25. 50 and 75 μm Diodes-



**Defect spectroscopy after PS p-irradiation**

**Generation of shallow donors BD (Ec-0.23 eV) strongly related to [O] Possibly caused by O-dimers, dimers monitored by IO<sub>2</sub> complex**

### SIMS profiling:

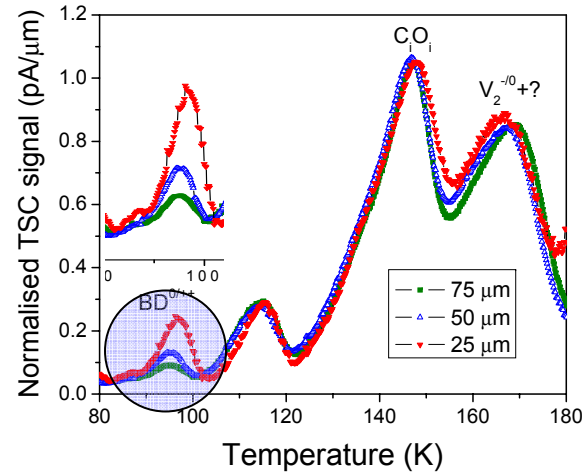
**[O](25μm) > [O](50μm) > [O](75μm)**

### Stable Damage:

**N<sub>eff</sub>(25μm) > N<sub>eff</sub>(50μm) > N<sub>eff</sub>(75μm)**

### TSC Defect Spectroscopy:

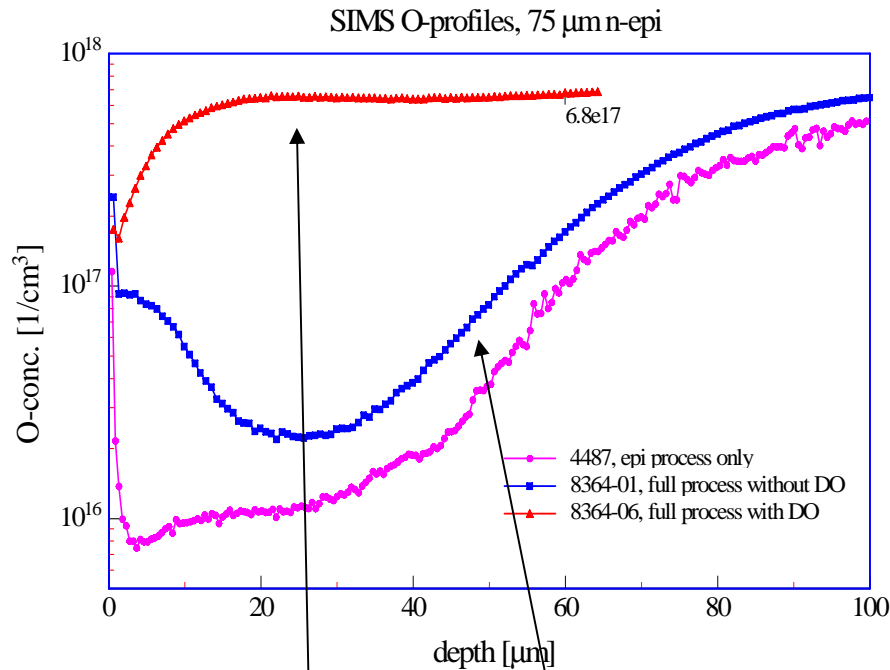
**[BD](25μm) > [BD](50μm) > [BD](75μm)**



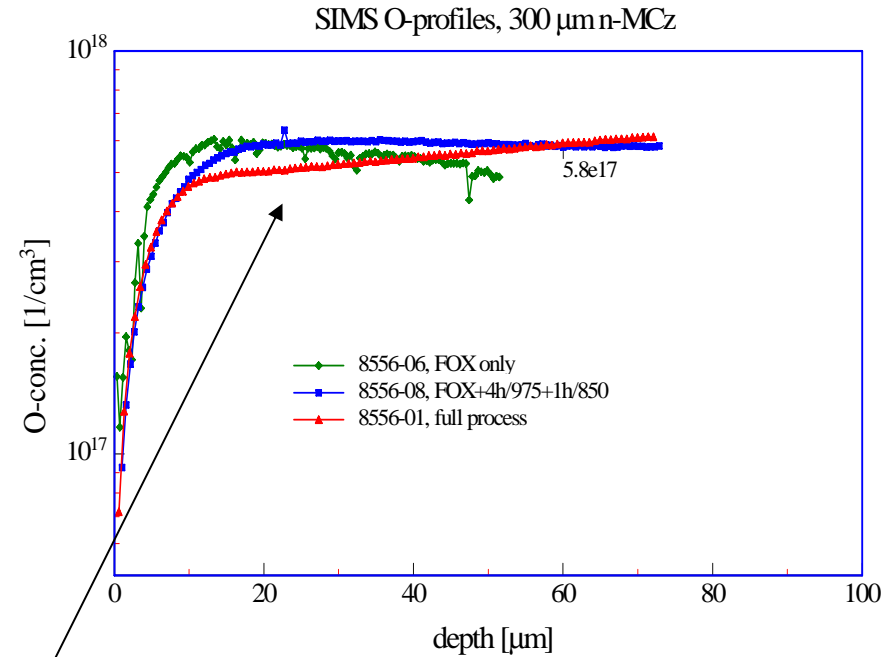
**Strong correlation between [O]-[BD]-g<sub>c</sub> generation of O (dimer?)-related BD reason for superior radiation tolerance of EPI Si detectors**



# Material



4487, 8364-01, 8364-06 / 29.5.2006



8556, 300  $\mu\text{m}$  N-MCZ / 29.5.2006

Epi/Cz: n-type, 145  $\Omega\text{cm}$ , 75  $\mu\text{m}$  on 300  $\mu\text{m}$  Cz-substrate, Cis process

(with and without DO)

MCZ: n-type, 880  $\Omega\text{cm}$ , 300  $\mu\text{m}$ , Cis process



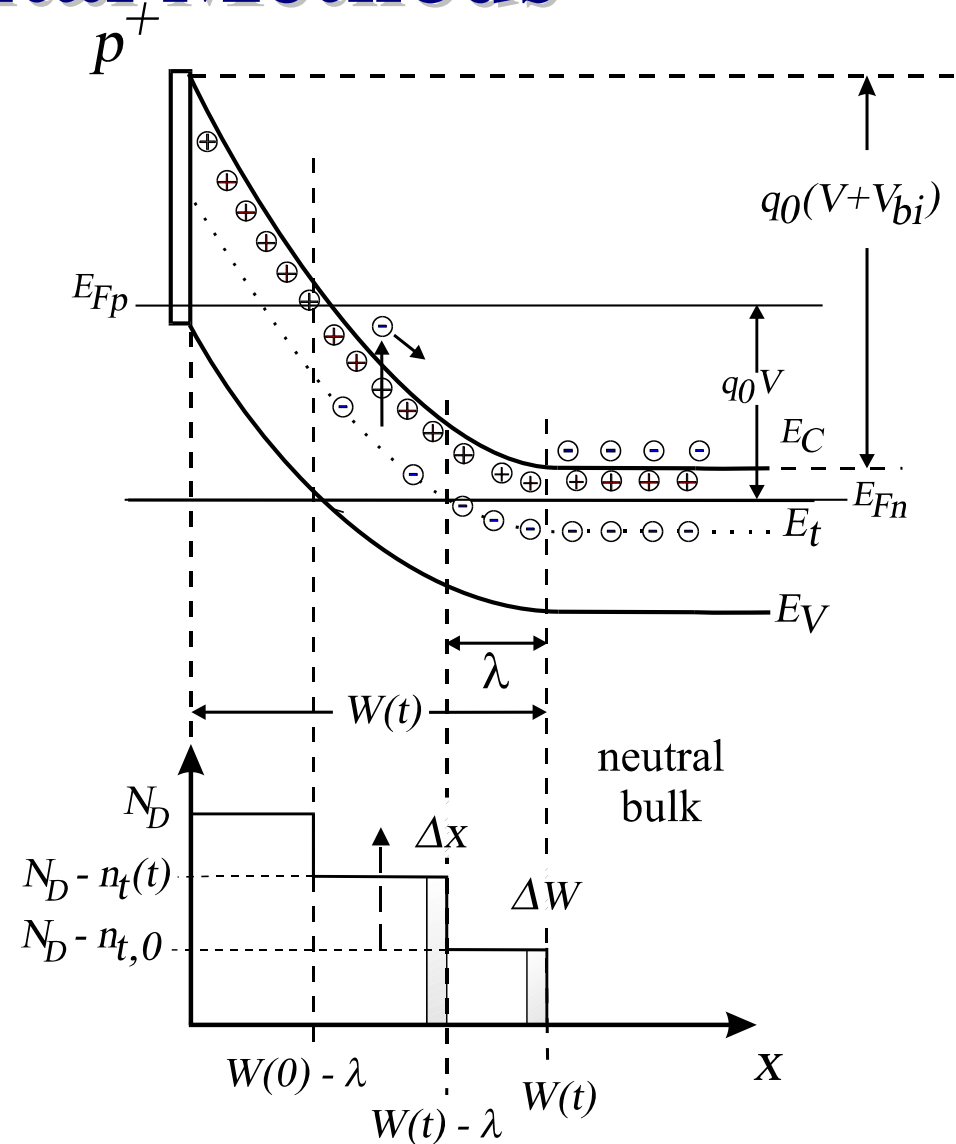
# Experimental Methods

**Irradiation source:**

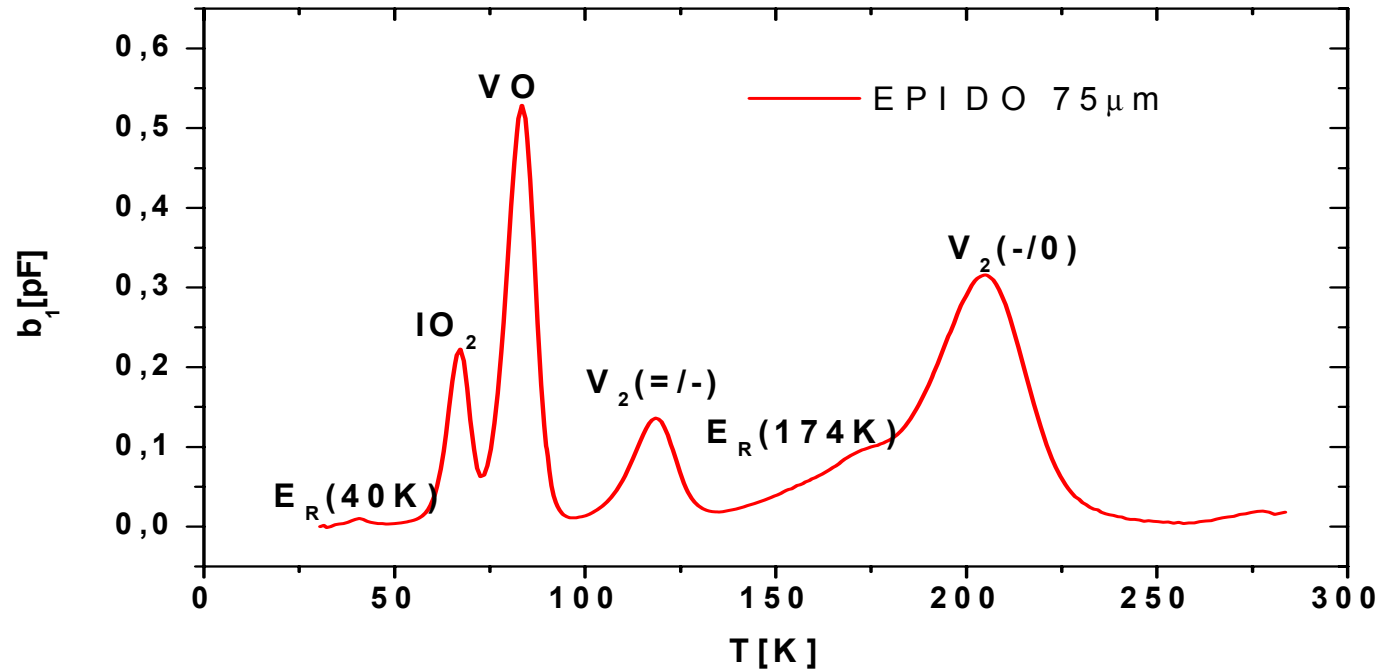
**26 MeV protons**

- Defect characterisation by C-DLTFS
- Measurement of depth profile taking transition region into account.

$$N_t = 2N_D \frac{\Delta C_0}{C_R} \left[ 1 - \left( \frac{C_R}{C_P} \right)^2 - \frac{2\lambda C_R}{\epsilon \epsilon_0 A} \left( 1 - \frac{C_R}{C_P} \right) \right]^{-1} \approx 2N_D \frac{|\Delta C_0|}{C_R}$$



# DLTS Spectra

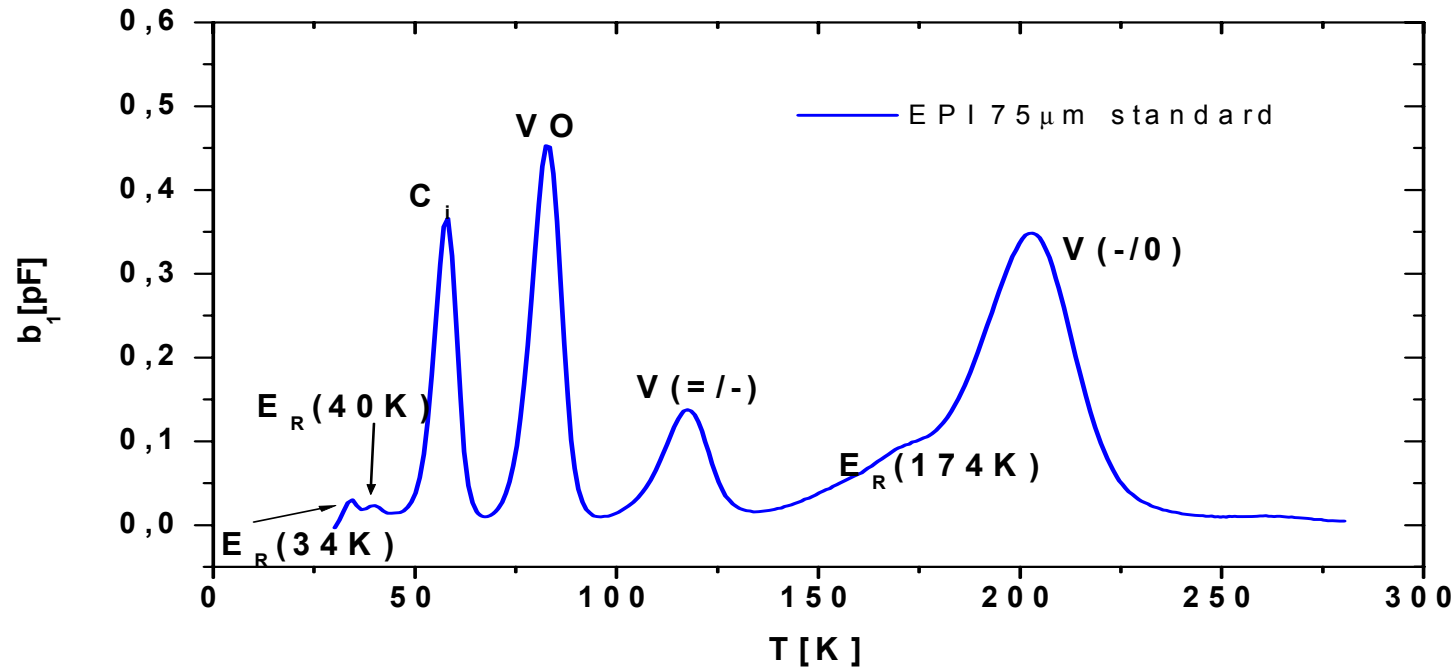


## EPI DO:

- $\Phi_{eq} = 8.2 \times 10^{11} \text{ cm}^{-2} \text{ p}^+ 26 \text{ MeV}$
- $U_R = -20\text{V}, U_P = -0.1\text{V}$
- $T_W = 200\text{ms}, T_P = 100\text{ms}$



# DLTS Spectra

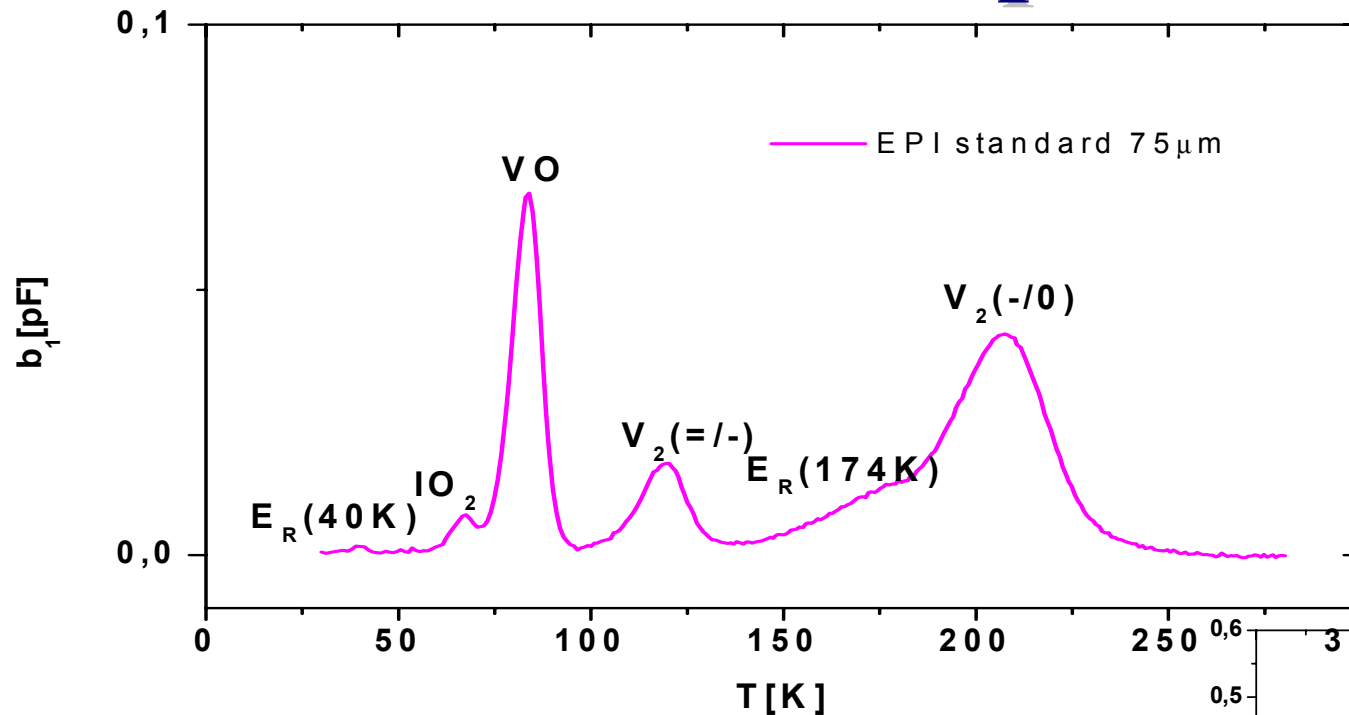


## EPI standard:

- $\Phi_{eq} = 8.0 \times 10^{11} \text{ cm}^{-2} \text{ p}^+ \text{ 26 MeV}$
- $U_R = -20\text{V}, U_p = -0.1\text{V}$
- $T_W = 200\text{ms}, T_p = 100\text{ms}$

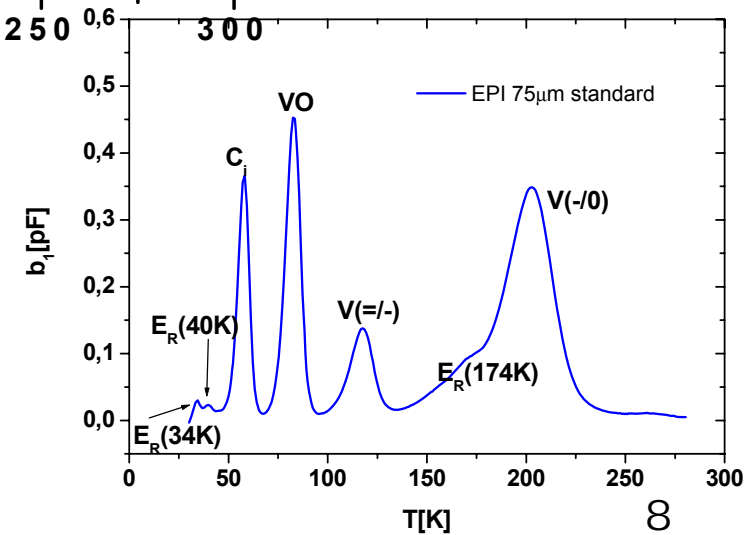


# DLTS Spectra



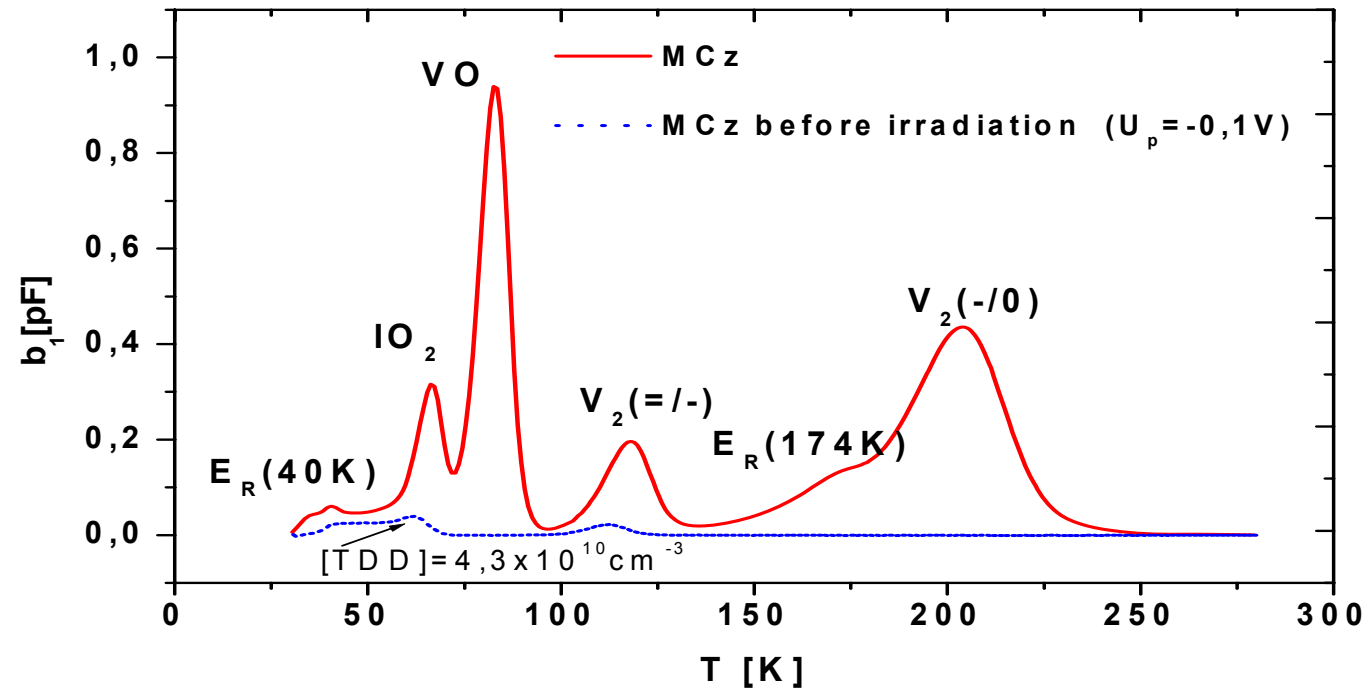
## EPI standard (backside):

- $\Phi_{eq} = 8.0 \times 10^{11} \text{ cm}^{-2} \text{ p}^+ \text{ 26 MeV}$
- $U_R = -80V, U_P = -60V$
- $T_W = 200ms, T_P = 100ms$





# DLTS Spectra

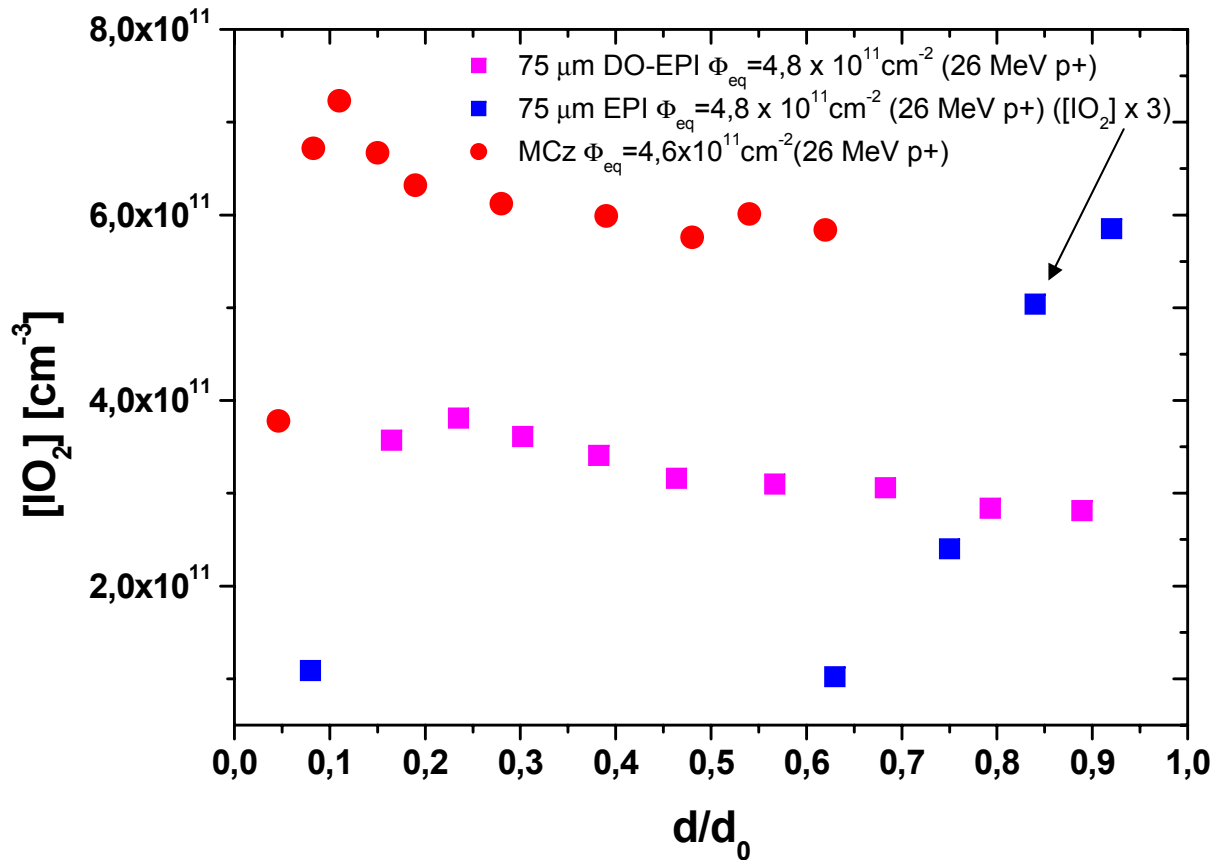


## MCZ:

- $\Phi_{eq} = 4.6 \times 10^{11} \text{ cm}^{-2} \text{ p}^+ 26 \text{ MeV}$
- $U_R = -20V, U_p = -5V$
- $T_W = 200\text{ms}, T_p = 100\text{ms}$



# Depth profil $IO_2$

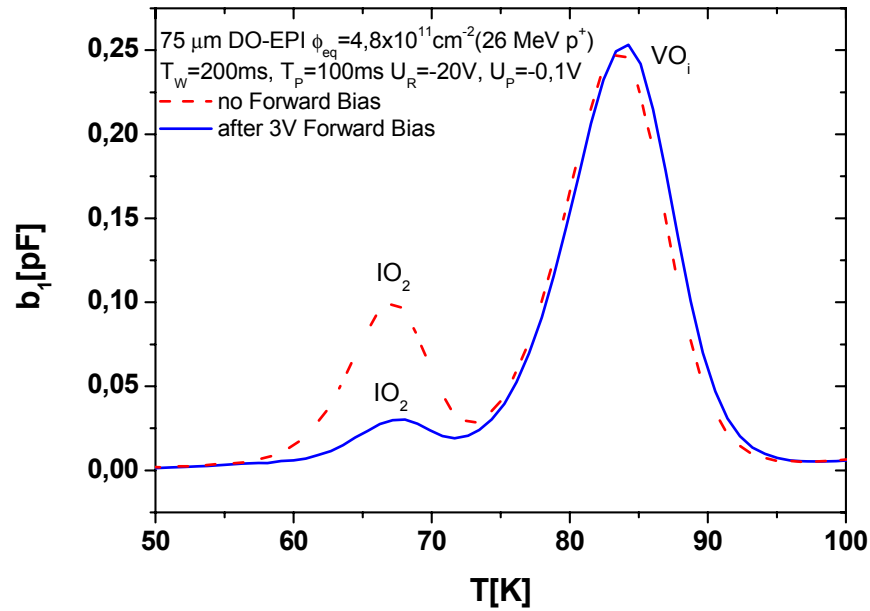


In DO-EPI and MCZ  
 $[IO_2]$  is almost  
 homogeneous like  $[O]$

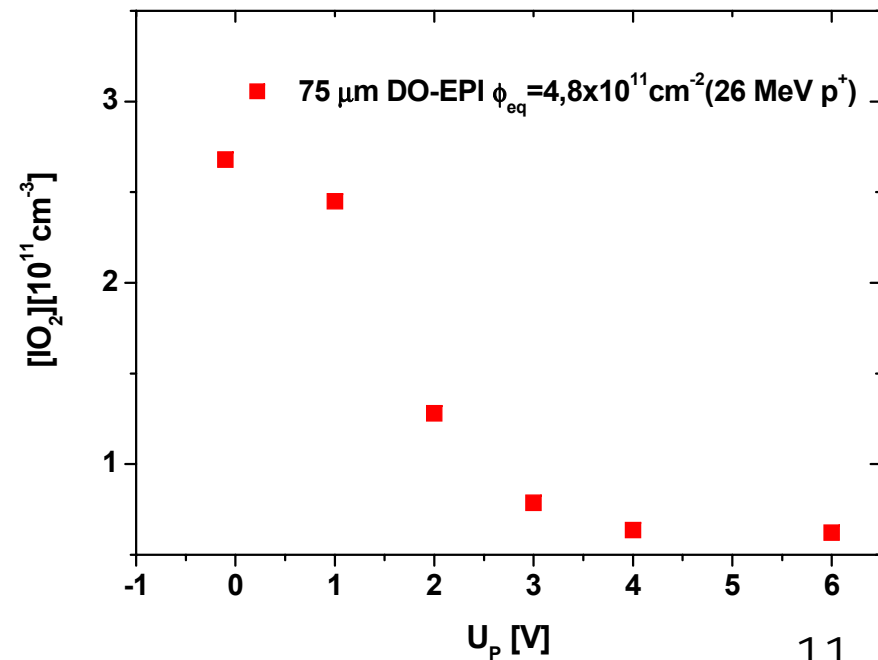
In EPI standard  $[IO_2]$  is  
 strongly inhomogeneous  
 like  $[O]$



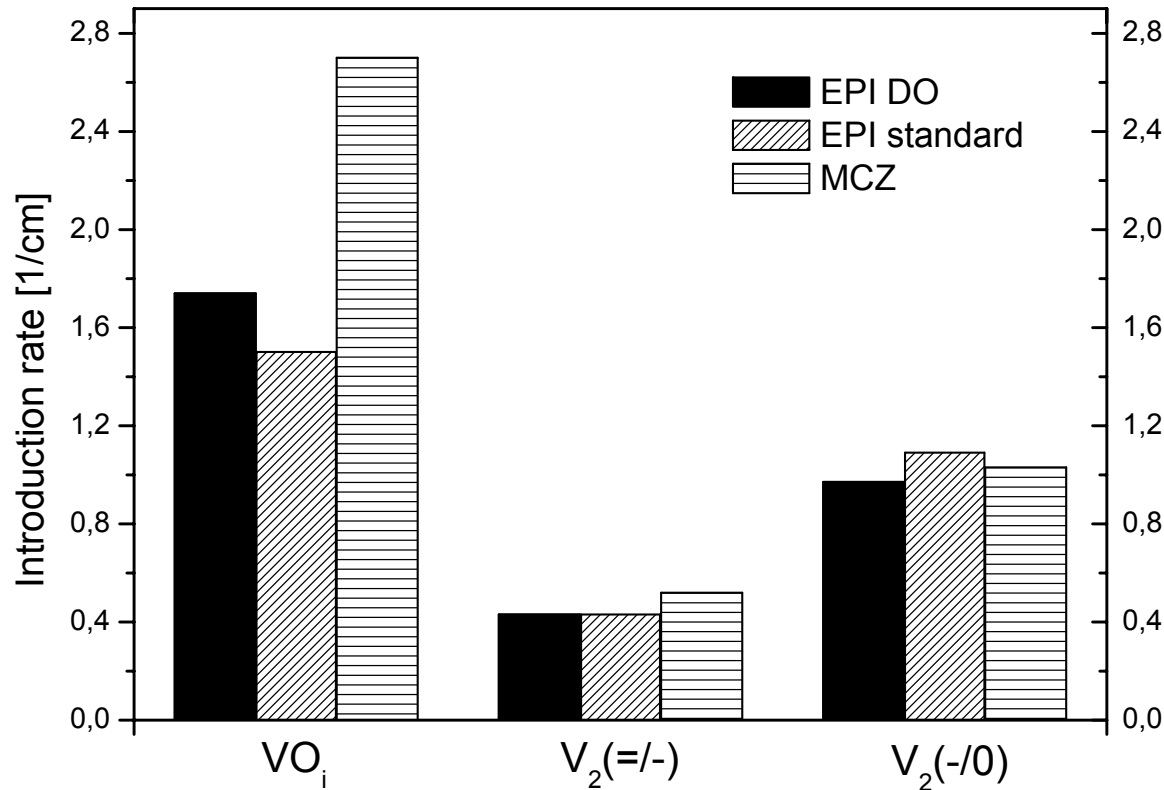
# Bistability of IO<sub>2</sub>



Change of state by forward biasing



# Introduction rates



## VO:

Similar introduction rate like for 23 GeV p+ irradiation

MCZ is higher after 26 MeV p+ irradiation.

## $V_2(=/-)$ :

Similar introduction rate like for 23 GeV p+ irradiation

## $V_2(-/0)$ :

Introduction rate is only half of what was found after 23 GeV p+ irradiation





# Conclusions

- New Epi materials show high [O] and high [IO<sub>2</sub>] like in MCZ
- Depth characteristics of [IO<sub>2</sub>] corresponds with [O]
- IO<sub>2</sub> defect shows bistability
- Introduction rates of vacancy related defects are nearly the same for investigated materials

